Workshop on

"*High Vacuum, Plasma & Thin Film Deposition for IC Technology*"

By

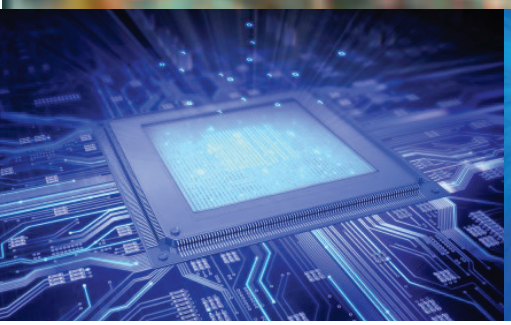
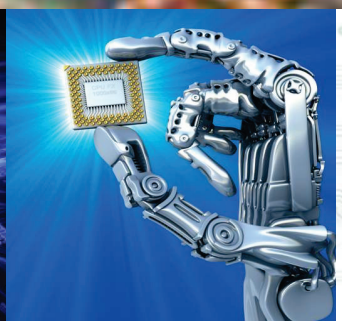
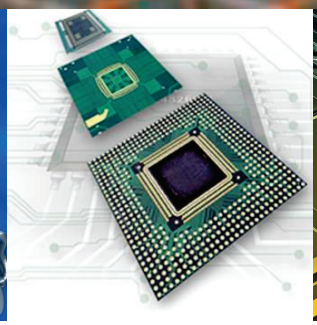
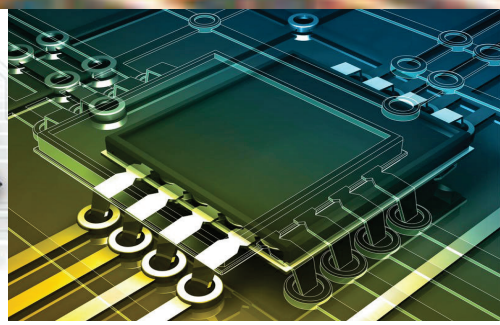
Eminent Scientist, TECHNOLOGY APPLICATIONS SERVICE

and GAUTAM BUDDHA UNIVERSITY

Scheduled from 7th to 9th Feb, 2013

Venue

School of ICT, Gautam Buddha University
Greater Noida.

Workshop Chairperson
Dr. Ela Kumar, Dean SICT,
GBU, Gr. Noida, India.

Workshop Convener
Mr. Navaid Zafar Rizvi,
SICT, GBU, Gr. Noida, India.

Registration is free and only about 50 participants will be invited on first come, first serve basis (through email only).

Talk sessions and Experiments include

Vacuum Techniques: Explanation about basic vacuum related concepts and components.

Plasma Characterization: Analysis of Plasma parameters such as Plasma potential, floating potential, electron temperature, ion density etc. using Langmuir probe.

DC Magnetron Sputtering Deposition: Utilizing Argon / Air demonstration of ZnO sputtered films

Vacuum Thermal Deposition: Al/Cu etc. deposition.

The Practical Hand on sessions, experiments and seminars will be conducted by Dr. R.K. Garg, Technology Applications Service, New Delhi.

Dr. Garg has more than 40 years of R&D experience in several areas of Integrated Circuits Design and its Fabrication. This experience includes 19 years in CSIR Laboratories (CEERI, Pilani and CSIO Chandigarh), 2 years in IIT Delhi, 7 years in CNRS Laboratories, Toulouse, France (world's first high voltage electron microscope) and Fritz Haber Institute of Max Planck Society, Berlin, Germany, a Group of late Prof. E. Ruska – Nobel Laureate in electron microscopy and University of Reims, France.

- **DEADLINE FOR REGISTRATION: 5th Feb, 2013 (24:00 IST)**
- **For participation consent and enquiry mail to navaid@gbu.ac.in**
- **Final list of the invited participants will be intimated through emails only.**

Gautam Buddha University
Greater Noida, NCR, India.